

	Hits	Search Text	DBs
41	6	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) and (resin\$3 same (cyclic or water\$3soluble or alkali\$3soluble or aromatic or alicyclic or heterocyclic or polyphenol or naphthalene\$3polyhydroxy or benzophenone or flavonoid or polycycloalkane or (aromatic near3 carboxylic) or cycloalkane) same ((alkali\$3 or water) near2 solub\$5)) and (surfactant near4 (nonionic or cationic) near19 (weight near5 ratio)) and (polyvinyl)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
42	6	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) and (resin\$3 same (cyclic or water\$3soluble or alkali\$3soluble or aromatic or alicyclic or heterocyclic or polyphenol or naphthalene\$3polyhydroxy or benzophenone or flavonoid or polycycloalkane or (aromatic near3 carboxylic) or cycloalkane) same ((alkali\$3 or water) near2 solub\$5)) and (surfactant near4 (nonionic or cationic) near19 (weight near5 ratio)) and (polyvinyl near6 (acetal or alcohol or acetate or pyrrolidone))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
43	117	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) and (resin\$3 same (cyclic or water\$3soluble or alkali\$3soluble or aromatic or alicyclic or heterocyclic or polyphenol or naphthalene\$3polyhydroxy or benzophenone or flavonoid or polycycloalkane or (aromatic near3 carboxylic) or cycloalkane) same ((alkali\$3 or water) near2 solub\$5)) and (surfactant near4 (nonionic or cationic)) and (polyvinyl near6 (acetal or alcohol or acetate or pyrrolidone)) and (ArF near22 (resist or photoresist)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
44	1	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) and (resin\$3 same (cyclic or water\$3soluble or alkali\$3soluble or aromatic or alicyclic or heterocyclic or polyphenol or naphthalene\$3polyhydroxy or benzophenone or flavonoid or polycycloalkane or (aromatic near3 carboxylic) or cycloalkane) same ((alkali\$3 or water) near2 solub\$5)) and (surfactant near4 (nonionic or cationic) near19 (gram or weight or g/110g or "g")) and (polyvinyl near6 (acetal or alcohol or acetate or pyrrolidone)) and (ArF near22 (resist or photoresist)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
45	125	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) and (resin\$3 same (cyclic or water\$3soluble or alkali\$3soluble or aromatic or alicyclic or heterocyclic or polyphenol or naphthalene\$3polyhydroxy or benzophenone or flavonoid or polycycloalkane or (aromatic near3 carboxylic) or cycloalkane) same ((alkali\$3 or water) near2 solub\$5)) and (surfactant near19 (gram or weight or g/110g or "g")) and (polyvinyl near6 (acetal or alcohol or acetate or pyrrolidone)) and (ArF near22 (resist or photoresist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
46	1	((resist or photoresist) same (pattern\$4 or structure or material or composition or (thicken\$4 near2 material))) and (resin\$3 same (cyclic or water\$3soluble or alkali\$3soluble or aromatic or alicyclic or heterocyclic or polyphenol or naphthalene\$3polyhydroxy or benzophenone or flavonoid or polycycloalkane or (aromatic near3 carboxylic) or cycloalkane) same ((alkali\$3 or water) near2 solub\$5)) and (surfactant near19 (gram or weight or g/110g or "g") near23 (nonionic or anionic or amphoteric or cationic)) and (polyvinyl near6 (acetal or alcohol or acetate or pyrrolidone)) and (ArF near22 (resist or photoresist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

